

Magnetron sputtering unit NIKA-149



The machine for coating N9 (nickel) (Nika-2012-500 N9) is designed for sputtering a coating of nickel (Ni) with a thickness of 9 μm (Chem. crossed fields).

The vacuum chamber of the installation is equipped with the following technological devices:

- ion source IBS-125
- ring magnetron;
- carousel with rotation of satellites with product carriers;
- IBS flap;
- magnetron shutter;
- temperature sensor;
- two viewing windows

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Layout and characteristics



Ring magnetron- 1
pc.



IBS-125 – Ion Beam
Source- 1 pc.

Parameters

Power	20 kWt
Supply voltage	380 V
Connecting to the network	TN-S
Maximum power consumption	19 kWt
Time to reach working vacuum	no more than 30 minutes
Number of gas injection channels	1
Maximum current consumption by phase	32 A
Weight	no more than 550 kg
Coolant volume	no more than 15 l
Ultimate vacuum	no more than 3×10^{-4} Pa
Working gases	argon, nitrogen, air
Working vacuum	6×10^{-3} Pa



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